

Fig. 1

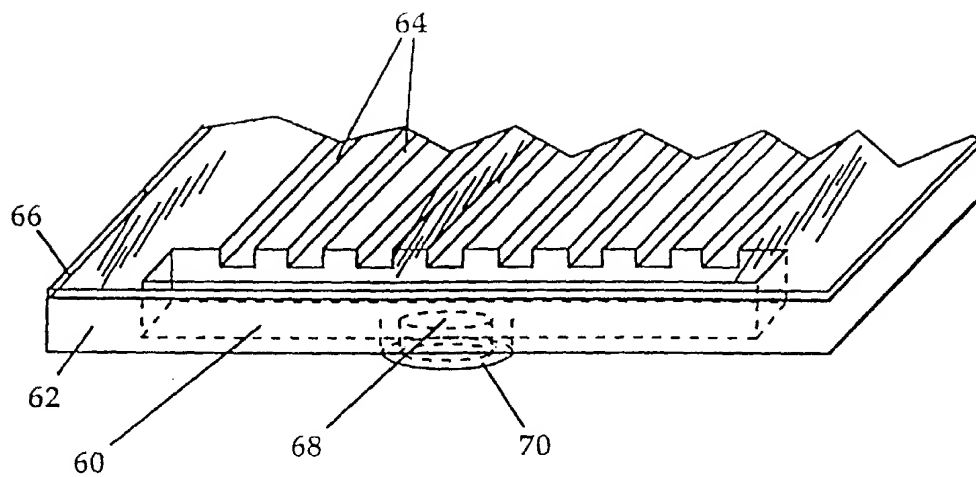


Fig. 2

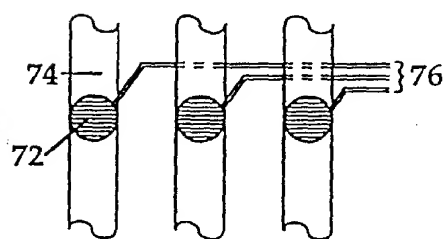


Fig. 3A

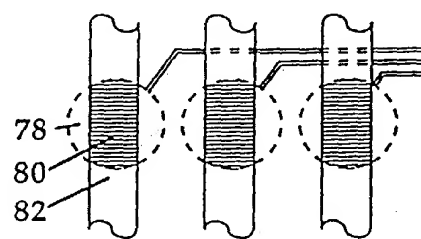


Fig. 3B

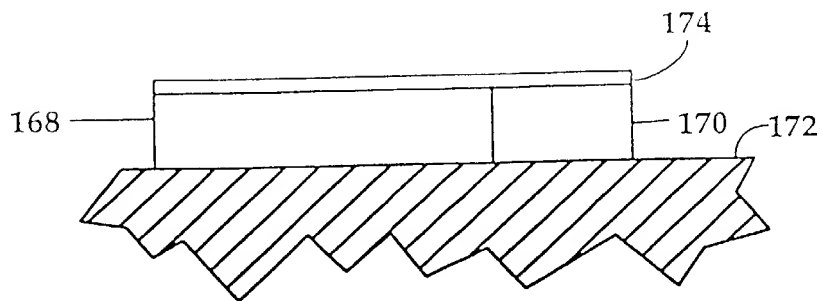


Fig. 4A

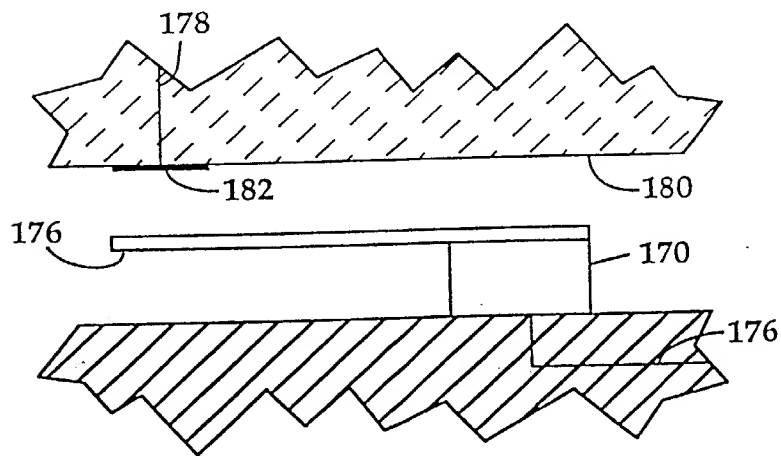


Fig. 4B

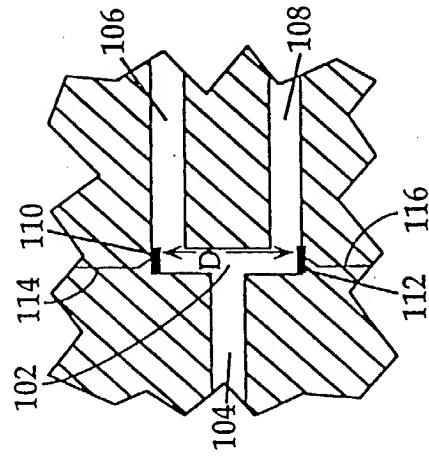


Fig. 5A

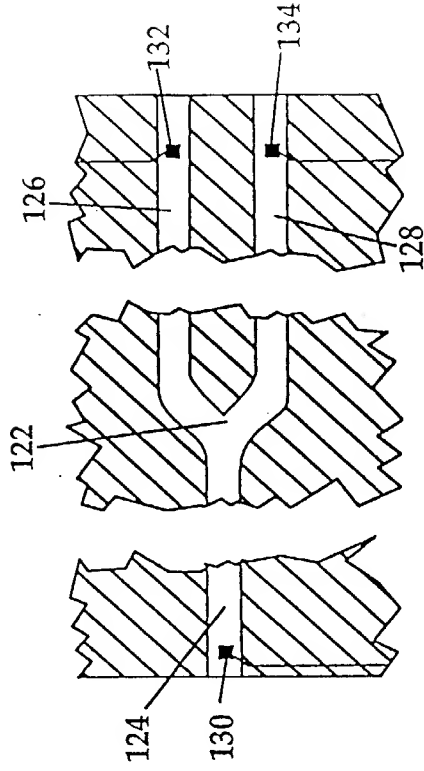


Fig. 5B

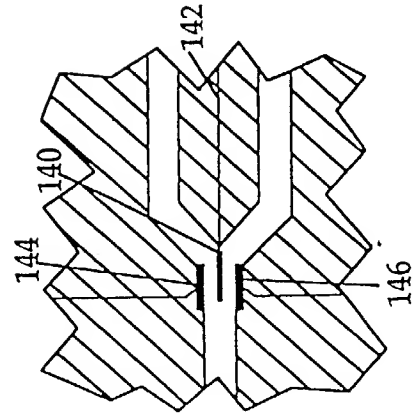


Fig. 5C

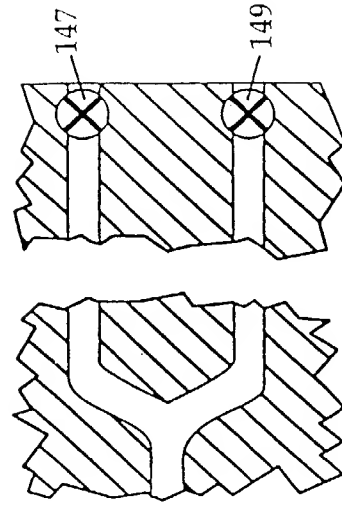


Fig. 5D

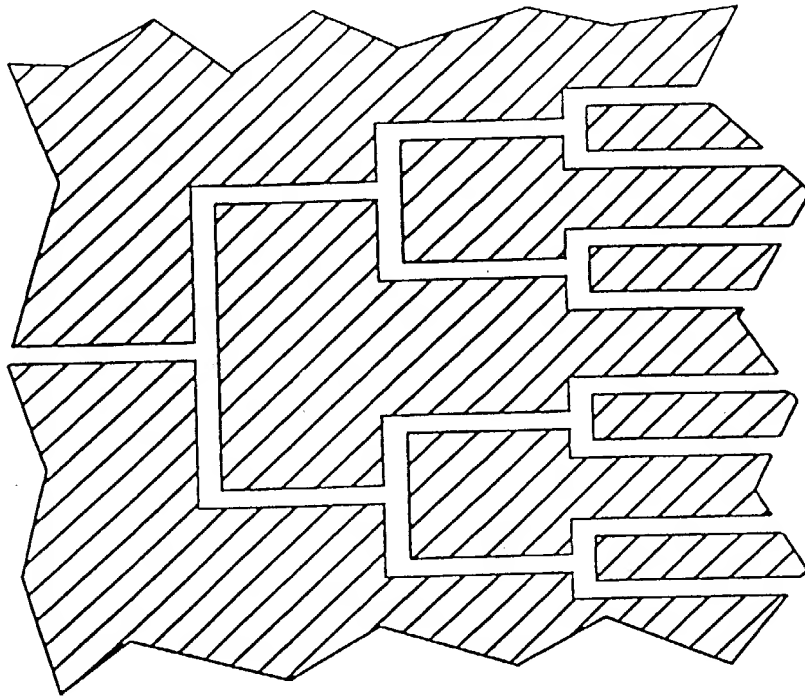


Fig. 6

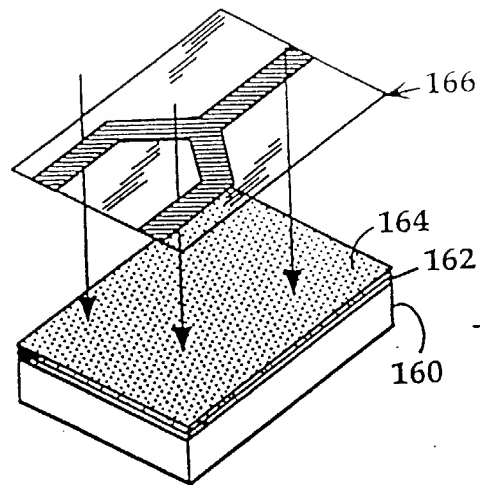


Fig. 7A

develop  
and rinse

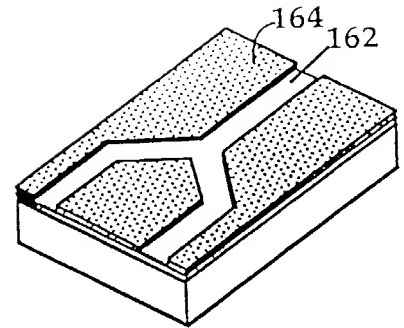


Fig. 7B

1. etch  $\text{SiO}_2$   
2. remove resist

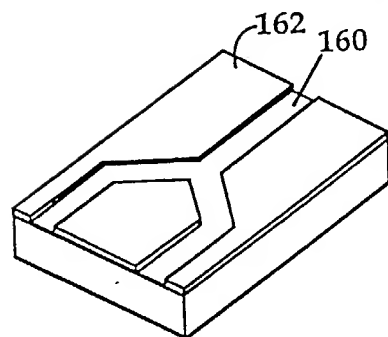


Fig. 7C

etch Si

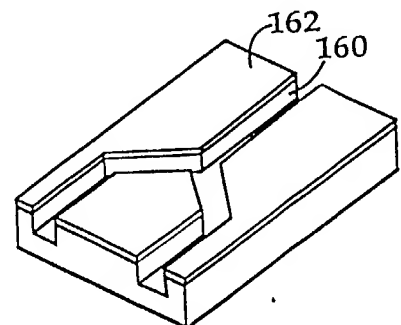


Fig. 7D

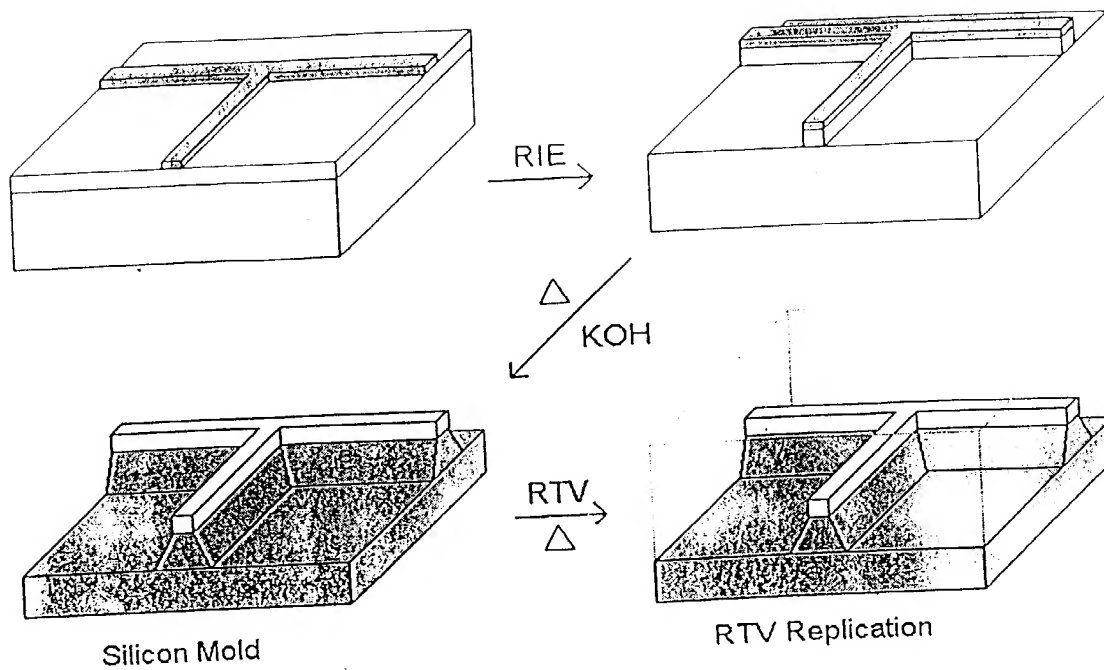
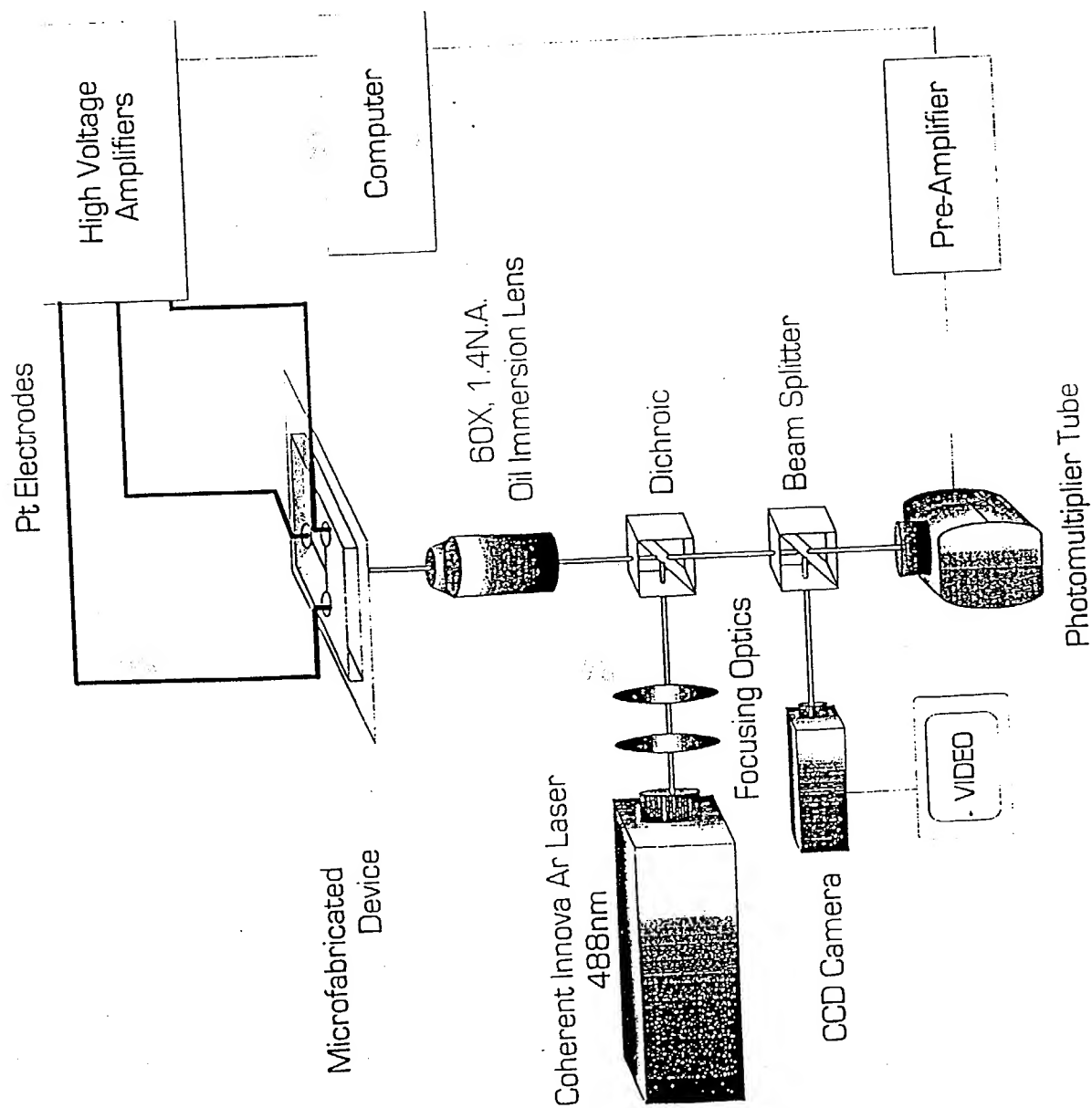


Fig. 8



Fid 9

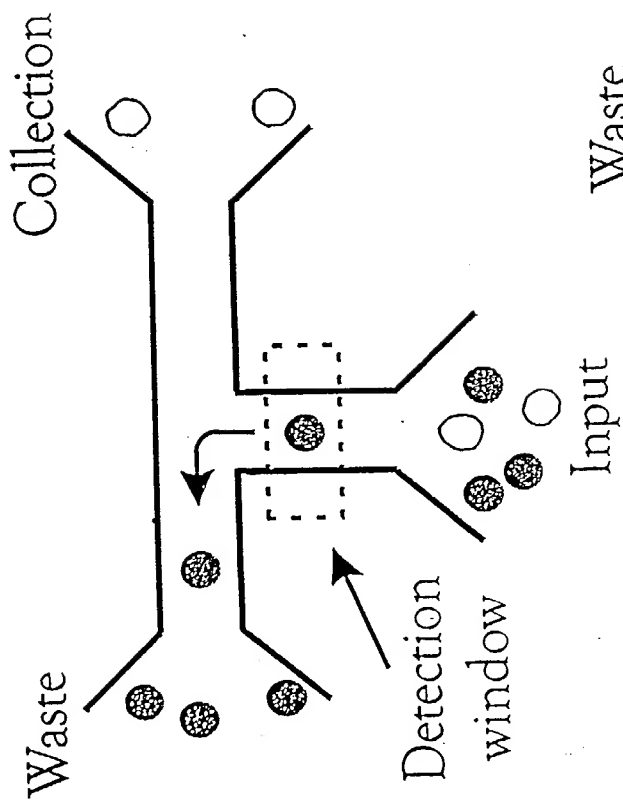


00826373-010100

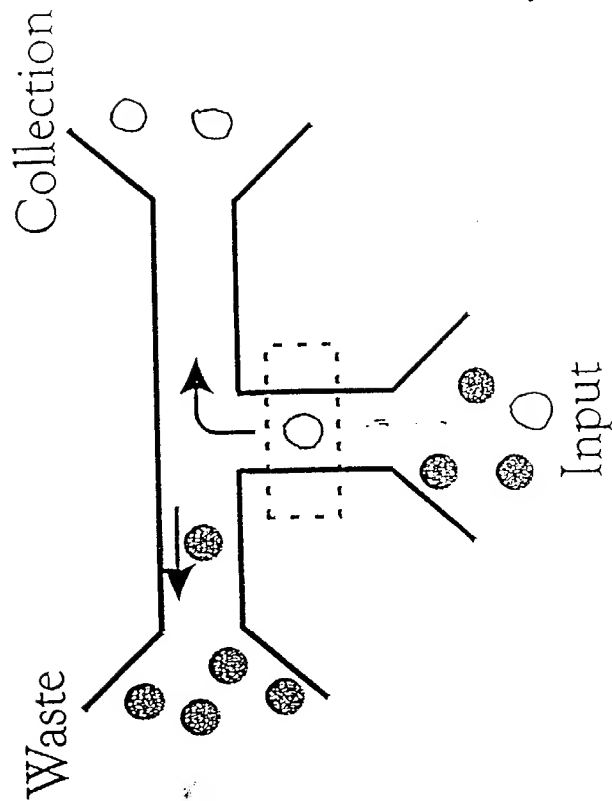


Fig 10

Fig. 11

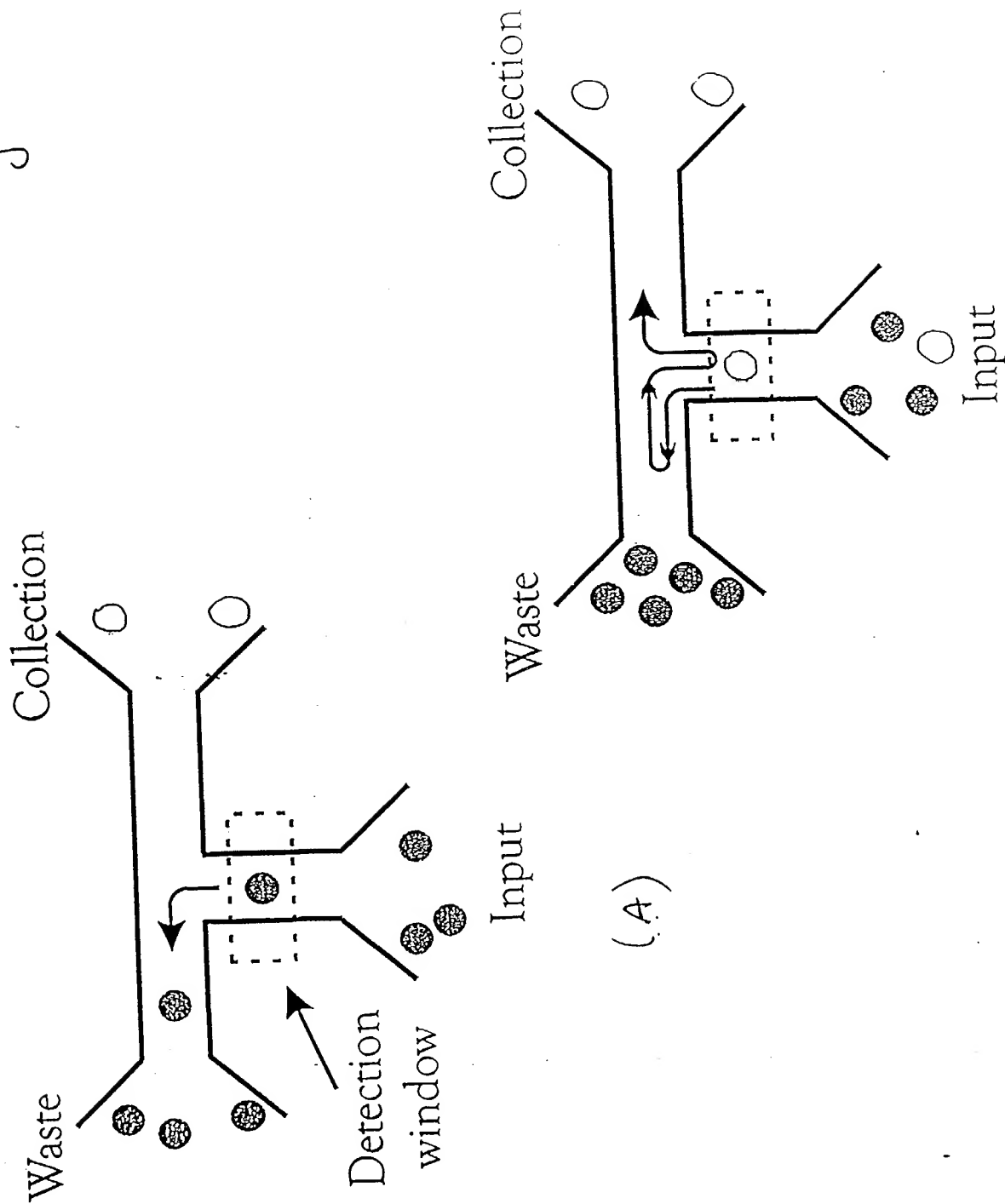


(A)



(B)

Fig 12



(B)

(A)

# T7 DNA/ T7 Primer

3.45mW laser power/ 2.450kV APD bias

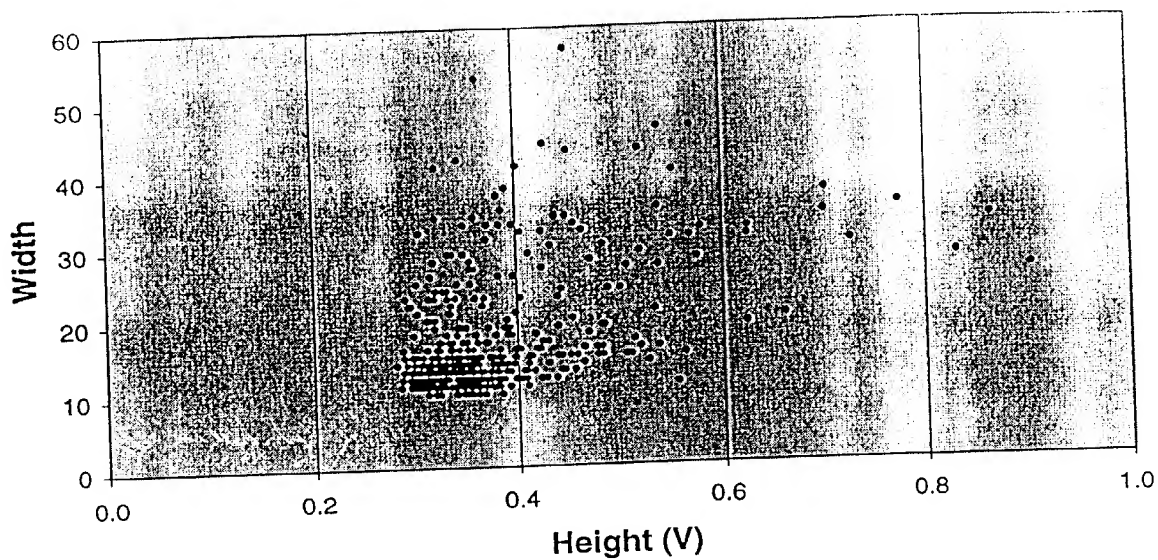


FIG. 13

# $\lambda$ DNA/ T7 Primer

3.35mW laser power/ 2.450kV APD bias

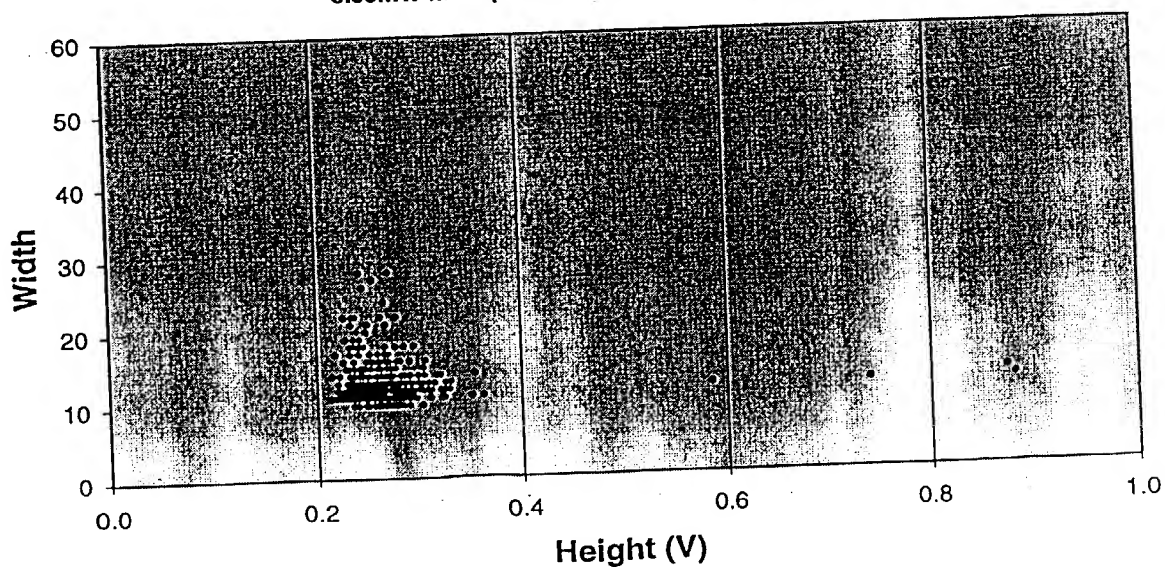


FIG. 14

# DNA/Primer Diagnosis

## Molecular Diagnostics

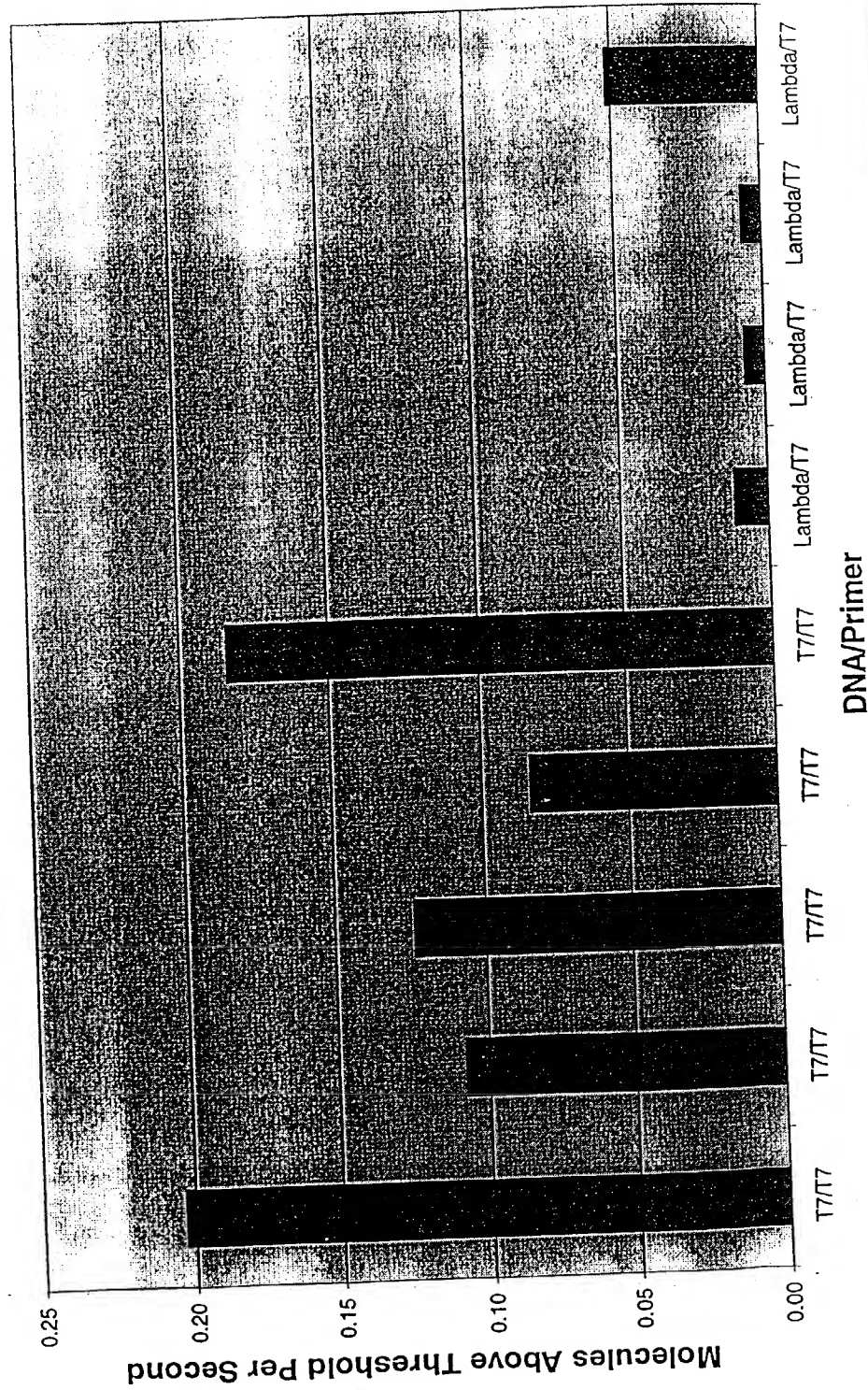


FIG. 15